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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 1

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Complete if Known								
Application Number	09/512,942							
Filing Date	February 25, 2000							
First Named Inventor	Theodore H. Fedynyshyn							
Art Unit	1752							
Examiner Name	Chu							
Attorney Docket Number	101328-0148							

			U.S. PA	TENT DOCUMENTS			
Examiner Initials*	Cite No.	Document Number  Number-Kind Code <sup>2</sup> ( if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, When Relevant Passages or Relevan		
Sec		3148983-B1	09-15-1964	Endermann, et al.	Figures Appear		
		3869292-B1	<del></del>	Peters			
		4115128-B1		Kita, N.			
		4246374-B1		Kopchik, R.			
		4377631-B1	03-22-1983	Toukhy, et al.			
		4404272-B1	09-13-1983	Stahlhofen, P.			
	<u> </u>	4404357-B1	09-13-1983	Taylor, et al.			
		4423138-B1	12-27-1983	Guild, J.			
	ļ	4424315-B1	01-03-1984	Taylor, et al.			
		4439516-B1	03-27-1984	Cernigliaro, et al.			
		4491628-B1		Ito, et al.			
	ļ	4791171-B1	12-13-1988	Cunningham, W.			
	ļ	4931379-B1	01-05-1990	Brunsvold, et al.			
	ļ	4939070-B1		Brunsvold, et al.			
	ļ	5047313-B1		Nebe et al.			
<u> </u>		6096479-B1	08-01-2000	Kawamura et al.			

	FOREIGN PATENT DOCUMENTS										
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document  Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear						
De-		JP-A 05015772-A1	01-26-1993			$\vdash$					
0		JP-A 63077952-A1	04-08-1988	ito, M.		$\vdash$					

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	NON PATENT LITERATURE DOCUMENTS										
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>								
785		Baidina, I., Podberezskaya, N., Borisov, S., Alekseev, V., Martynova, I., and Kanev, A. Zh. Strukt. Khim. 21, 125 (1980).									
<u> </u>		Clegg, W., Sheldrick, G., and Vater, N. Acta Crystallogr. 38B, 3162 (1980).	<del>                                     </del>								
		Kloster-Jensen, E., and Rimming, C. Acta Chem. Scand. 40B, 604 (1986).	+								
		Mertesdor, C., et al. Microelectronics Technology, 1995, Pp. 35-55.									
V		Brinker et al., Sol-Gel Science, Academic Press, Inc. p. 97									

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Examiner Signature	1	C	Date Considered	12/	2001
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<sup>&#</sup>x27;Applicant's unique citation designation number (optional). <sup>3</sup>Applicant is to place a check mark here if English language Translation is attached. 1306993.1

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY. DOCKET NO: APPLICATION NO: (Rev. 8-83) PATENT AND TRADEMARK OFFICE 101328-148 09/512,942 INFORMATION DISCLOSURE CITATIONE APPLICANT: Theodore H. Fedynyshyn TECHNULUS CENTED FOR DATE: (Use several sheets if necessary) GROUP ART UNIT: February 25, 2000 2852 **U.S. PATENT DOCUMENTS** EXAMINER DOCUMENT NUMBER DATE INITIAL FILING DATE IF NAME **CLASS** SUBCLASS APPROPRIATE\* 2 04/74 Moreau 96 115R AB 2 0 2 6 9 7 05/80 Van Goethem et al. 430 306 FOREIGN PATENT DOCUMENTS TRANSLATION DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS YES NO BA 0 0 8 01/89 Japan abst BB 9 03/91 Japan X OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.) CA 🗸 Bruschi, P. et al., "Gas Sensing with Conducting Polymer Thin Film Resistors Obtained From Commercial Photoresist Patterns," Sens. Microsyst., Proc. Ital. Conf., Di Natale et al. (Editors), 69-73 (1996); Crivello, J. and Mao, Z., "Preparation and Cationic Photopolymerization of Organic-Inorganic Hybrid Matrixes," CB: Chem. Mater., vol. 9, 1562-69 (1997); Dagani, R., "Putting the 'Nano' into Composites," Chemical, 25-37 (June 7, 1999); CC Dumpich, G. et al., "Direct Writing of Metallic Nanostructures by Means of Metal Colloids," Materials Science CD. Forum, vols. 287-8, 413-6 (1998); Kaplan, L.H. and Zimmerman, S.M., "Enhanced E-Beam Sensitivity of Resist," IBM Technical Disclosure Bulletin, vol. 21, no. 7, p. 2823 ( December 1978); Mucha, et al., "Plasma Etching of Materials Used in Microelectronic Manufacturing," Introduction to Microlithography, L. Thompson et al., (editors), 449-64 (1994); Pu, Jia-Ling et al., "Photobinding of Colloidal Particles by Means of Surface Modification," Journal of Imaging Science, vol.32, no. 3, 129-34 (May/June 1988); Pu, Jia-Ling et al., "Photobinding of Colloidal Particles by Means of Surface Modification. II. Surface Azido Density and Dispersibility," Journal of Imaging Science, vol.32, no.6, 232-7 (November/December 1988); Examiner Date Considered: \*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and considered. Include copy of this form with next communication to applicant. #873514v1 < imanage > -ids 1449.wpd

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMIN

ATTY. DOCKET NO: 101328-148

APPLICATION NO: 09/512,942

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

APPLICANT: Theodore H. Fedynyshyn

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	CI ✓	Voss	meyeı	r, Τ. ε	t al.,	"Ligh	t-Dire	cted A	Assembly of	Nanopartic	les," Angew.	Chem. Int.	Ed Enol	vol. 36, no. 10,
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